# **Beam Profiles from Multiple Aperture Sources**

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## BEAM PROFILES FROM MULTIPLE APERTURE SOURCES

#### J. H. Whealton

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#### ABSTRACT

Using a rapidly convergent approximation scheme, formulas are given for beam intensity profiles everywhere. In first approximation, formulas are found for multiple aperture sources, such as a TFTR design, and integrated power for rectangular plates downstream for Gaussian beamlets. This analysis is duplicated for Lorentzian beamlets which should provide a probable upper bound for off-axis loading as Gaussian beamlets provide a probable lower bound. Formulas for beam intensity profiles are found everywhere. In first approximation, formulas are found for downstream intensity of multiple sources and integrated power for rectangular plates. Previous analysis<sup>1</sup> includes formulas for the beam power intensity for Gaussian beamlets at (a) the focal plane, (b) on the beam axis, and (c) very near the beam axis. By considering a rapidly convergent approximation scheme these results are extended to give beam power intensities everywhere and, in first approximation, beam intensities everywhere for multiple, but closely spaced, sources. Total beam power deposited on a rectangular plate is also given.

Consider the coordinate system and approximation scheme shown in Fig. 1 where the circular source is approximated by a square one. The intensity at a point  $\zeta$ ,  $\eta$ ,  $\xi$  from an element in the source is

$$di(\zeta,n,\xi) = \frac{1}{\pi(\xi\theta)^2} \exp\left[-\frac{(\zeta^2 + \eta^2)}{(\xi\theta)^2}\right] d\zeta dn, \qquad (1)$$

and the intensity at a point  $\zeta$ ,  $\eta$ ,  $\xi$  from the entire source, in first approximation, is

$$1_{1}(\zeta,\eta,\xi) = \frac{1}{\pi(\xi\theta)^{2}} \int_{-1/2}^{+1/2} d\zeta' \int_{-1/2}^{+1/2} d\eta' \exp\left[-\frac{(\zeta'-\zeta)^{2}+(\eta'-\eta)^{2}}{(\xi\theta)^{2}}\right].$$
 (2)

Integration gives the result:

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$$i_{1}(\zeta,\eta,\xi) = \frac{1}{4} \left[ \operatorname{erf} \left( \frac{1-2\zeta}{2\xi\theta} \right) + \operatorname{erf} \left( \frac{1+2\zeta}{2\xi\theta} \right) \right] \\ \times \left[ \operatorname{erf} \left( \frac{1-2\eta}{2\xi\theta} \right) + \operatorname{erf} \left( \frac{1+2\eta}{2\xi\theta} \right) \right].$$
(3)

If focusing is considered as in the above figure, i is divided by  $(1 - \xi/\lambda)^2$  and the limits of integration in Eq. (2) are multiplied by  $1 - \xi/\lambda$  giving the result, in first approximation,

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$$i_{1}(\zeta,\eta,\xi) = \frac{\lambda^{2}}{4(\lambda-\xi)^{2}} \left\{ erf\left[\frac{\lambda(1-2\zeta)-\xi}{2\lambda\xi\theta}\right] + erf\left[\frac{\lambda(1+2\zeta)-\xi}{2\lambda\xi\theta}\right] \right\}$$

$$\times \left\{ erf\left[\frac{\lambda(1-2\eta)-\xi}{2\lambda\xi\theta}\right] + erf\left[\frac{\lambda(1+2\eta)-\xi}{2\lambda\xi\theta}\right] \right\},$$
(4)

which at the focal plane, using the asymptotic properties of the error function, becomes in any approximation

$$\mathbf{i}(\zeta,\eta,\lambda) = \frac{1}{\pi(\xi\theta)^2} \exp\left[-\frac{\zeta^2 + \eta^2}{(\xi\theta)^2}\right], \qquad (5)$$

in agreement with previous analysis.<sup>1</sup> On the axis the intensity becomes in first approximation

$$i_{1}(0,0,\xi) = \frac{\lambda^{2}}{(\lambda - \xi)^{2}} \left[ \operatorname{erf} \left( \frac{\lambda - \xi}{2\lambda\xi\theta} \right) \right]^{2} , \qquad (6)$$

in contrast with the exact results in the previous analysis,

$$\mathbf{1}(0,0,\xi) = \frac{\lambda^2}{\left(\lambda - \xi\right)^2} \left\{ 1 - \exp\left[-\frac{\left(\lambda - \xi\right)^2}{\pi\left(\lambda\xi\theta\right)^2}\right] \right\} . \tag{7}$$

In second approximation, as shown in Fig. 1, two square sources are considered at 45° to each other. The result it

$$i_{2}(\zeta,n,\xi) = \frac{1}{2} i_{1}(\zeta,n,\xi) + \frac{1}{2} i_{1}\left(\frac{\zeta+n}{\sqrt{2}}, \frac{n-\zeta}{\sqrt{2}}, \xi\right), \qquad (8)$$

and so on for the n<sup>th</sup> approximation,

$$\mathbf{i}_{n}(\zeta,\eta,\xi) = \frac{1}{n} \sum_{m=0}^{n-1} \mathbf{i}_{1}\left(\zeta \cos \frac{m\pi}{2n} + \eta \sin \frac{m\pi}{2n}, \eta \cos \frac{m\pi}{2n} - \zeta \sin \frac{m\pi}{2n}\right)$$
(9)

For multiple sources (e.g., three) the total beam intensity at a point is in first approximation:

$$i_{III}(\zeta,\eta,\xi) = i_{1}(\zeta,\eta,\xi) + i_{1}[\zeta,\eta - \alpha(\lambda - \xi),\xi] + i_{1}[\zeta,\eta + \alpha(\lambda - \xi),\xi] ,$$
(10)





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. . . . .

where the configuration of the three sources is shown in Fig. 2.

Finally the integrated power is computed from a single source in first approximation over the hatched area in Fig. 3, which is

$$\int_{\beta}^{\infty} d\zeta \int_{-\gamma}^{+\gamma} d\eta \, i_{1}(\zeta,\eta,\xi) = \frac{\lambda^{2}}{2(\lambda-\xi)^{2}} g(\gamma) \, g(-\beta)$$
(11)

where

$$g(\gamma) = \xi \theta \left( \left[ \frac{\lambda(1+2\gamma)}{2\lambda\xi\theta} - \zeta \right] \text{ orf } \left[ \frac{\lambda(1+2\gamma)}{2\lambda\xi\theta} \right] - \left[ \frac{\lambda(1-2\gamma)}{2\lambda\xi\theta} \right] \exp \left\{ - \left[ \frac{\lambda(1+2\gamma)}{2\lambda\xi\theta} - \frac{\xi}{2\lambda\xi\theta} \right]^2 + \frac{1}{\sqrt{\pi}} \exp \left\{ - \left[ \frac{\lambda(1+2\gamma)}{2\lambda\xi\theta} - \frac{\xi}{2\lambda\xi\theta} \right]^2 \right\} \right\}$$

$$+ \frac{1}{\sqrt{\pi}} \exp \left\{ - \left[ \frac{\lambda(1-2\gamma)}{2\lambda\xi\theta} - \frac{\xi}{2\lambda\xi\theta} \right]^2 \right\} \right\}, \qquad (12)$$

the extension to three sources being obvious.

The inaccuracy of the first approximation is clearly very small near the focal plane and larger outside.

Perhaps it is worthwhile to note that the analysis in first approximation is directly applicable to the Berkeley source providing that the tensoral divergence angle is included by starting from

$$di(\varsigma,\eta,\zeta) = \frac{1}{\pi\theta_{\parallel}\theta_{\perp}\xi^{2}} \exp\left[-\left(\frac{\zeta^{2}}{\theta_{\parallel}\xi^{2}} + \frac{\eta^{2}}{\theta_{\perp}\xi^{2}}\right)\right] d\eta d\zeta ,$$

instead of Eq. (1).

An assumption in the foregoing is that individual beamlets have a Gaussian profile. Since such a profile has a very rapid off-axis falloff and since certain beam line designs may depend on wall loading, a Lorentzian beamlet profile is considered. A Lorentzian profile falls off more slowly off-axis as is seen in Fig. 4. The same approximation scheme and analysis as mentioned above is presented below for Lorentzian beamlets.

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Fig. 2. Three source configuration.

ORNL DWG 79-2035 FED



Fig. 3. Region of total power computation.

ORNL DWG 79-2036 FED 1.2 1.0 0.8 0.6 0.4 -x² GAUSSIAN, e 0.2 LORENTZIAN,  $\frac{a^2}{x^2 + a^2}$ , a<sup>2</sup> = 0.7 0 -1.5 -0.5 0 0.5 1.0 -1.0 1.5

Fig. 4. Comparison of Gaussian and Lorentzian.

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Consider the coordinate system and approximation scheme as shown in Fig. 1 where the circular source is approximated by a square one. The intensity at a point  $\zeta$ ,  $\eta$ ,  $\xi$  from an element in the source is

$$di(\zeta, \eta, \xi) = \frac{(\xi \theta / \pi)^2}{(\zeta^2 + \xi^2 \theta^2)(\eta^2 + \xi^2 \theta^2)} d\zeta d\eta , \qquad (13)$$

where the divergence angle  $\theta$  is the half max angle of the Lorentzian distribution along one axis. The beamlet distribution is not quite cylindrically symmetric but this artifact washes out in higher approximations. The intensity at a point  $\zeta$ ,  $\eta$ ,  $\xi$  from the entire source, in first approximation, is

$$i_{1}(\zeta, \eta, \xi) = \left(\frac{\xi\theta}{\pi}\right)^{2} \int_{-1/2}^{+1/2} d\zeta' \int_{-1/2}^{+1/2} d\eta' \left[ (\zeta' - \zeta)^{2} + \xi^{2} \theta^{2} \right]^{-1} \\ \times \left[ (\eta' - \eta)^{2} + \xi^{2} \theta^{2} \right]^{-1}.$$
(14)

Integration gives the result:

$$i_{1}(\zeta,\eta,\xi) = \frac{1}{\pi^{2}} \left[ \arctan\left(\frac{1-2\zeta}{2\xi\theta}\right) + \arctan\left(\frac{1+2\zeta}{2\xi\theta}\right) \right] \\ \times \left[ \arctan\left(\frac{1-2\eta}{2\xi\theta}\right) + \arctan\left(\frac{1+2\eta}{2\xi\theta}\right) \right].$$
(15)

If focusing is considered as in Fig. 1, i is divided by  $(1 - \xi \lambda)^2$  and the limits of integration in Eq. (14) are multiplied by  $1 - \xi/\lambda$  giving the result

$$i_{1}(\zeta,n,\xi) = \frac{(\lambda/\pi)^{2}}{(\lambda-\xi)^{2}} \left\{ \arctan\left[\frac{\lambda(1-2\zeta)-\xi}{2\lambda\xi\theta}\right] + \arctan\left[\frac{\lambda(1+2\zeta)-\xi}{2\eta\xi\theta}\right] \right\}$$
$$\times \left\{ \arctan\left[\frac{\lambda(1-2\eta)-\xi}{2\lambda\xi\theta}\right] + \arctan\left[\frac{\lambda(1+2\eta)-\xi}{2\lambda\xi\theta}\right] \right\}$$
(16)

which at the focal plane using the asymptotic properties of the arc tangent becomes

$$i_{1}(\zeta,\eta,\lambda) = \frac{(\lambda/\pi)^{2}}{(\zeta^{2} + \lambda^{2}\theta^{2})(\eta^{2} + \lambda^{2}\theta^{2})} \qquad (17)$$

On the axis the intensity becomes in first approximation

$$i_{1}(0,0,\xi) = \frac{4(\lambda/\pi)^{2}}{(\lambda-\xi)^{2}} \left[ \arctan\left(\frac{\lambda-\xi}{2\lambda\xi\theta}\right) \right]^{2} .$$
 (18)

In second approximation two square sources are considered at 45° to each other, as shown in Fig. 1.

For multiple sources (e.g., three) the total beam intensity at a point is approximately in first approximation by Eq. (10) where the configuration of the three sources is shown in Fig. 2.

Finally the integrated power is computer from a single source in first

$$\int_{\beta}^{\infty} d\zeta \int_{-\gamma}^{+\gamma} d\eta \, i_{1}(\zeta, \eta, \xi) = \frac{2(\lambda/\pi)^{2}}{(\lambda - \xi)^{2}} g(\gamma) \, g(-\beta) , \qquad (19)$$

$$g(\gamma) = \xi \theta \left( \left[ \frac{\lambda(1 + 2\gamma) - \xi}{2\lambda\xi\theta} \right] \arctan \left[ \frac{\lambda(1 + 2\gamma) - \xi}{2\lambda\xi\theta} \right] - \left[ \frac{\lambda(1 - 2\gamma) - \xi}{2\lambda\xi\theta} \right] \right) \times \arctan \left[ \frac{\lambda(1 - 2\gamma) - \xi}{2\lambda\xi\theta} \right] - \frac{1}{2} \log \left\{ (2\lambda\xi\theta)^{2} + [\lambda(1 + 2\gamma) - \xi]^{2} \right\} + \frac{1}{2} \log \left\{ (2\lambda\xi\theta)^{2} + [\lambda(1 - 2\gamma) - \xi]^{2} \right\} , \qquad (20)$$

the extension to three sources being obvious.

The inaccuracy of the first approximation is clearly very small near the focal plane and larger outside. As with the Gaussian beamlet case, it is worthwhile to note that the analysis in first approximation is directly applicable to the Berkeley source providing that the tensoral divergence angle is included by starting from

$$di(\zeta,\eta,\xi) = \frac{\xi^2 \theta_{||} \theta_{\perp} / \pi^2}{(\zeta^2 + \xi^2 \theta_{||}^2)(\eta^2 + \xi^2 \theta_{\perp}^2)} d\eta d\zeta .$$
(24)

This analysis was done in April 1976 and partially reported in Nuclear Instruments and Methods <u>141</u>, 187 (1977). At the time there was little evidence for fatter distributions than Gaussian. However, since that time such evidence has accumulated. In connection with reionization loss calculations accounting for direct beam interception, these calculations assume new importance and this report is issued in response to this demand.

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